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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Application Serial No. 09/783,377
Filing Date February 13, 2001
Inventor Vladimir Segal et al.
Assignee Honeywell International Inc.
Group Art Unit 1742
Examiner Combs, Janell A.
Attorney's Docket No. 30-5022 (4015)
Title: Methods of Forming Aluminum-Comprising Physical Vapor Deposition Targets;
Sputtered Films; and Target Constructions

SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

To: Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

From: Jennifer J. Taylor, Ph.D. (Tel. 509-624-4276; Fax 509-838-3424)
Wells St. John P.S.
601 W. First Avenue, Suite 1300
Spokane, WA 99201-3828

Dear Sir:

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449 and copies of which are attached.

Citation of these references is respectfully requested.

A check in the amount of \$180.00 is enclosed to cover the fee specified under 37 C.F.R. § 1.17(p).

Respectfully submitted,

Dated:

January 8, 2004

By:

Jennifer J. Taylor
Jennifer J. Taylor, Ph.D.
Reg. No. 48,711

LIST OF ART CITED BY APPLICANT
(Use several sheets if necessary)APPLICANT
Vladimir Segal et al.FILING DATE
February 13, 2001GROUP
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U.S. PATENT DOCUMENTS

*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
AA	6,423,161 B1	07-2002	Yao et al.			
AB	6,605,199 B2	08-2003	Perry et al.			
AC						
AD						
AE						
AF						
AG						
AH						
AI						
AJ						
AK						
AL						

FOREIGN PATENT DOCUMENTS

	Document Number	Date	Country	Class	Subclass	Translation	
						Yes	No
AM	EP 0 521 163 A1	01-1993	EPO				
AN							
AO							
AP							
AQ							

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)

AR		
AS		
AT		

EXAMINER

DATE CONSIDERED

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.